**Supporting information**

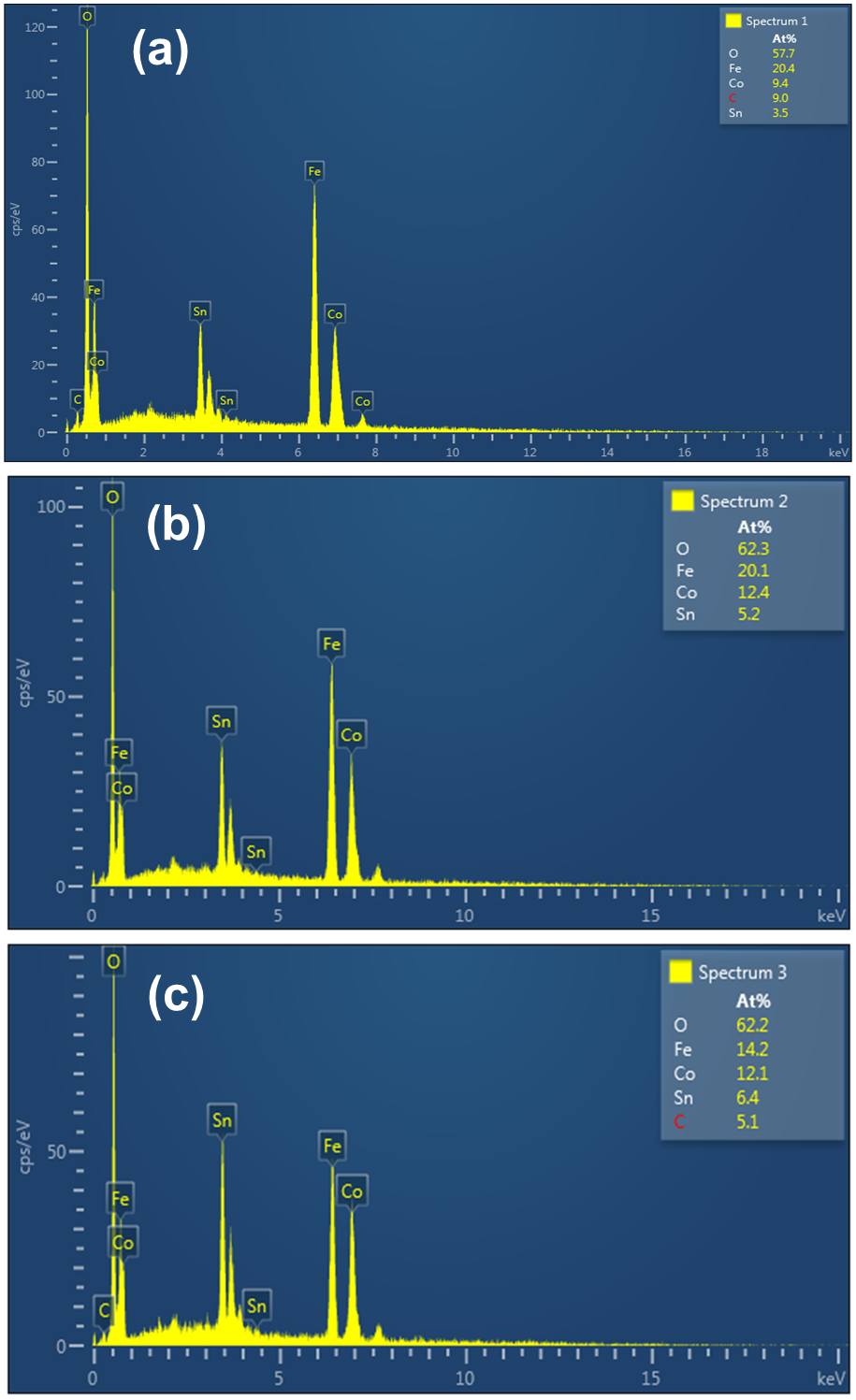
**The Pseudocapacitive Nature of CoFe2O4 Thin Films**

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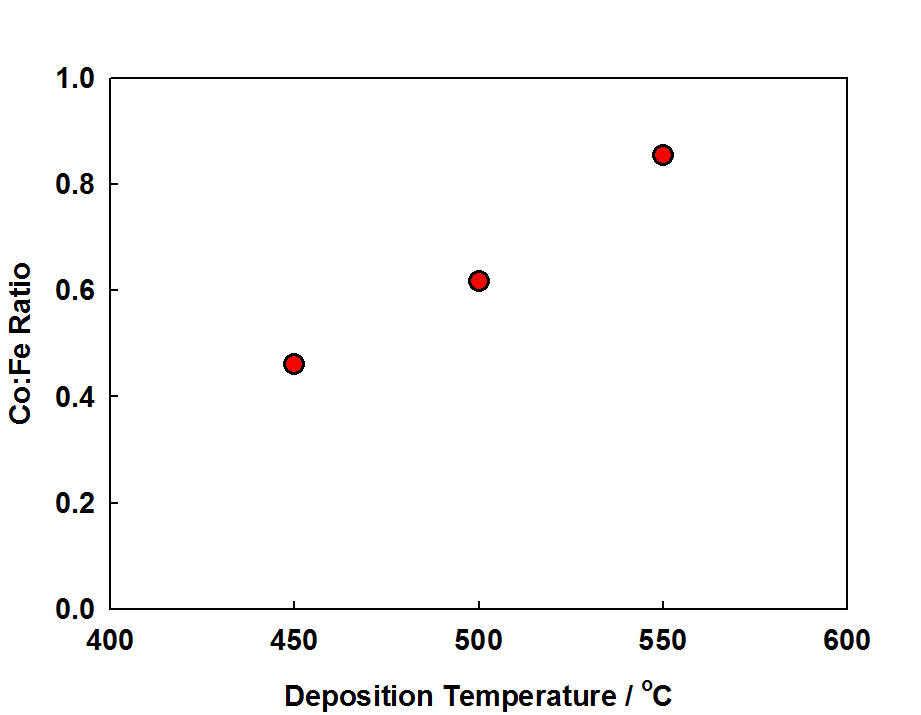
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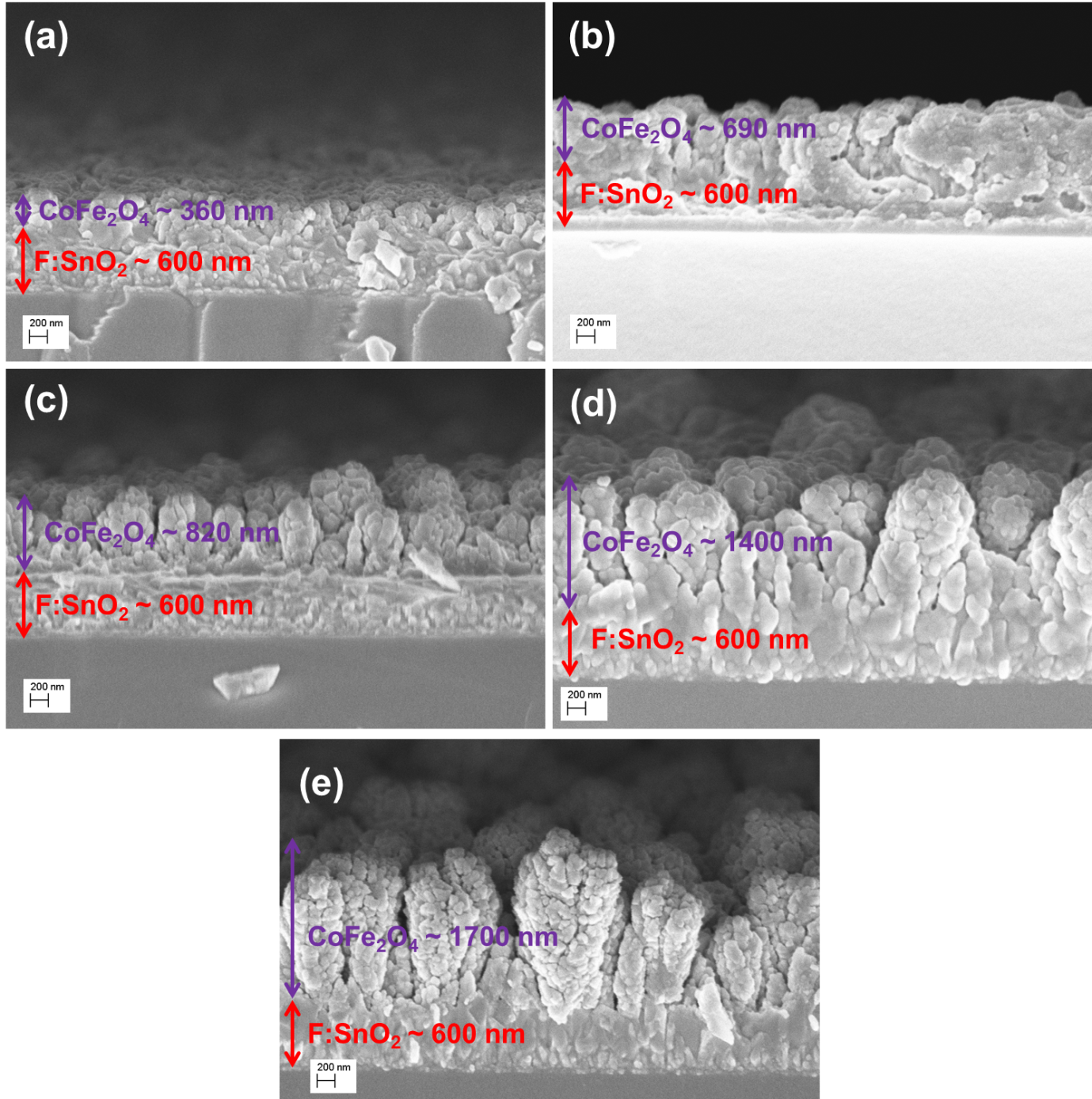
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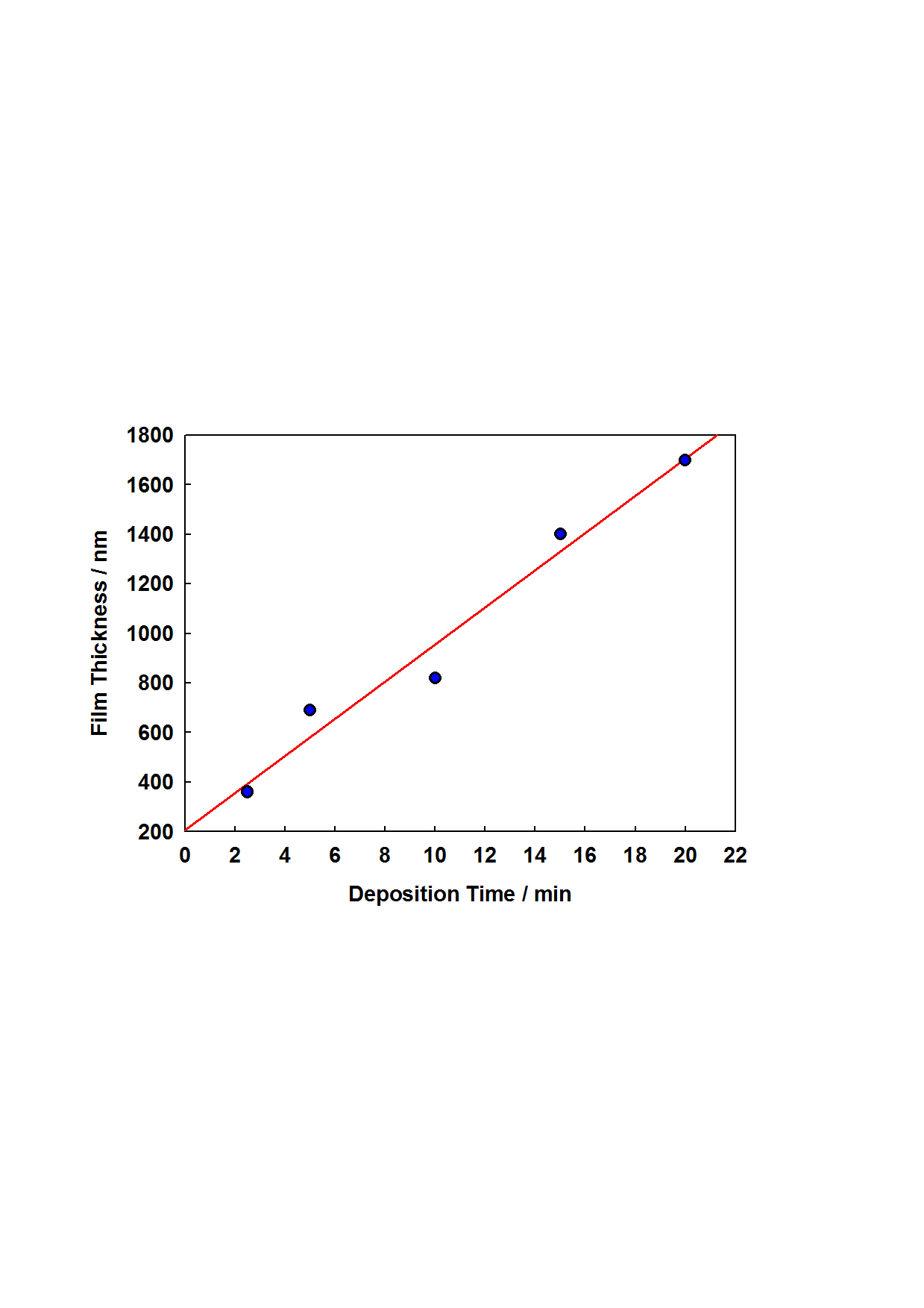
***Figure S1.*** EDX analysis of CoFe2O4 thin films deposited on FTO glass substrates for 20 min using AACVD at (a) 450oC, (b) 500oC and (c) 550oC. The Co:Fe ratio is **1:2.17**, **1:1.62** and **1:1.17** for films deposited at 450oC, 500oC and 550oC, respectively.



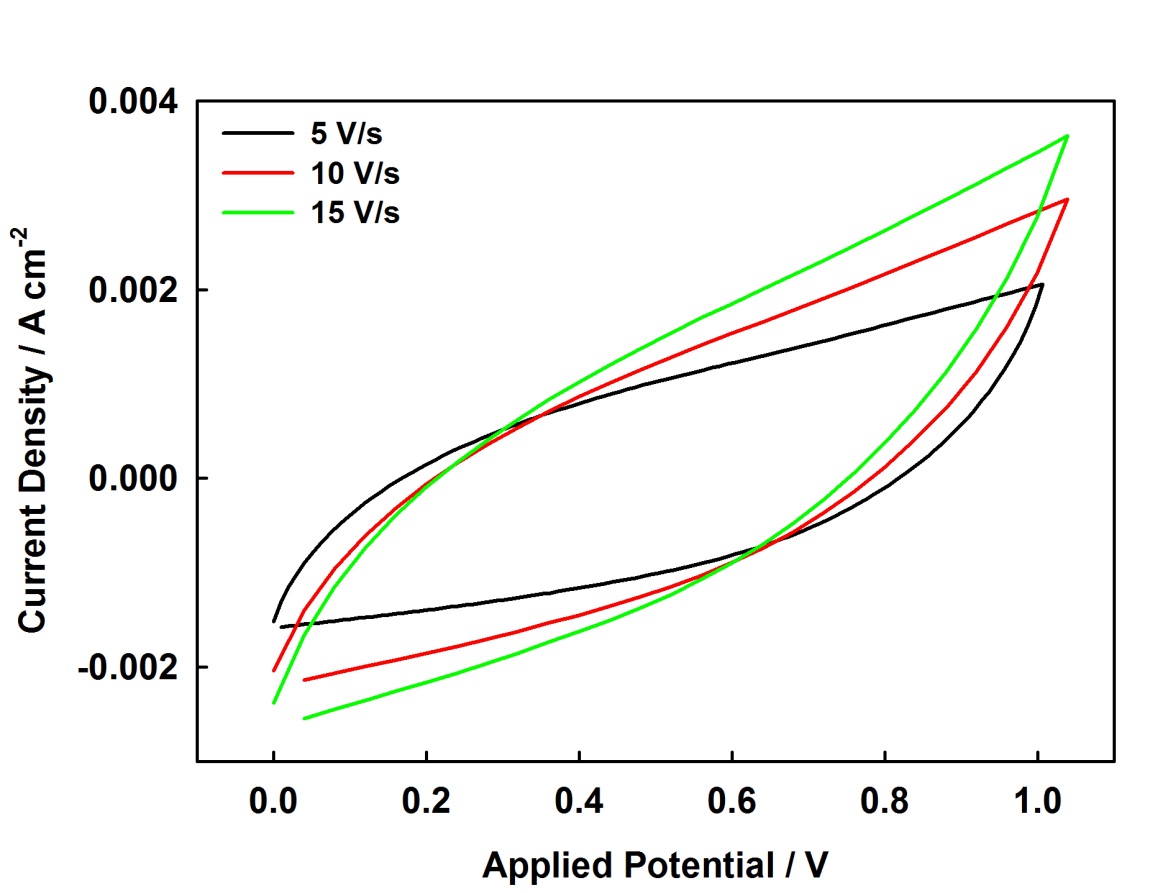
***Figure S2.*** Co:Fe ratio as a function of deposition temperature. Expected ratio for pure CoFe2O4 is 0.5.



***Figure S3.*** Cross-sectional SEM images of CoFe2O4 thin films deposited on FTO glass substrates at 550 oC using AACVD for (a) 2.5 min, (b) 5 min, (c) 10 min, (d) 15 min and (e) 20 min.



***Figure S4.*** CoFe2O4 film thickness as a function of AACVD deposition time at 550oC.



***Figure S5.*** Cyclic voltammograms of a CoFe2O4 symmetric supercapacitor in 1 M NaOH at fast scan rates of 5, 10 and 15 V/s.

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***Figure S6.*** Electrochemical response of a bare F:SnO2 substrate compared with a typical CoFe2O4 thin film prepared at 550oC using AACVD.